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(71)Applicant: NIPPON STEEL CHEM CO LTD

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(72)Inventor: FURUMOTO MASASHI

JIMI KAZUYOSHI

(54) PRODUCTION OF BISPHENOL COMPOUNDS

(57) Abstract:

PURPOSE: To improve the yield, reaction rate, selectivity, etc., of the bisphenol compound by modifying an acidic cation exchange resin charged into a reactor and used for the reaction with a nitrogen-containing sulfur compound so as to give an uniform modification degree over the whole packed bed.

CONSTITUTION: A method for producing the bisphenol compound such as bisphenol A by charging raw materials containing a carbonyl compound such as acetone and a phenol compound into a reactor filled in with an acidic cation exchange resin and reacting the raw materials with each other comprises once intermitting the reaction, charging a solution into the reactor for modifying the acidic cation exchange resin with a nitrogen-containing sulfur compound, and then restarting the reaction. The solution is produced by dissolving the nitrogen-containing sulfur compound in the mixed solvent of the phenol and/or the carbonyl compound with an organic compound having a specific dielectric constant of 1.8-5.0. The method enables to readily improve the performance of the acidic cation exchange resin, to improve the yield, selectivity, etc., of the bisphenol compound, and further to reduce or eliminate a mercaptan to be added to the raw materials.

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